WHAT IS CLAIMED IS:

1. A method for fabricating a liquid crystal display comprising:

forming a first substrate part having a gate line, a data line, a common voltage terminal, a contact area connected to the common voltage terminal, a thin film transistor and a pixel electrode, the contact area being provided at an edge portion of the first substrate part;

forming a second substrate part having a common electrode;

attaching the first and second substrate parts to each other to form attached substrates;

exposing the contact area at the edge of the first substrate part of the attached substrates; and

electrically connecting the contact area of the first substrate part to the common electrode of the second substrate part.

2. The method according to claim 1, wherein the exposing step comprises using an etch solution to remove an insulating layer formed over the contact area.

3. The method according to claim 2, wherein a side portion of the attached substrates is dipped into the etch solution to remove the insulting layer over the contact area.

4. The method according to claim 1, wherein electrically connecting the contact area to the common electrode uses a conductive material.

5. The method according to claim 1, wherein the exposing step comprises etching and removing an insulating layer formed over the contact area by using a laser.

6. The method according to claim 1, wherein the exposing step comprises etching and removing an insulating layer formed over the contact area by using plasma.

7. The method according to claim 1, wherein the step of forming the first substrate comprises:

forming a gate electrode and a gate line in a first direction on a substrate;

forming a first insulating layer over the substrate;

forming an active layer and an ohmic contact layer at a region on the insulating layer, the region corresponding to an area above the gate electrode;

forming source and drain electrodes on the ohmic contact layer and a data line in a second direction normal to the first direction;

forming a pixel electrode at least partially overlapped with and electrically connected with the drain electrode; and

forming a second insulating layer over the substrate including the pixel electrode.

8. The method according to claim 7, wherein the step of forming the active layer, the ohmic contact layer and the source and drain electrodes are performed using one mask.

9. The method according to claim 7, wherein only three masks are used to form the gate electrode, the first insulating layer, the active layer, the ohmic contact layer, the source and drain electrodes, the pixel electrode and the second insulating layer.

10. The method according to claim 7, wherein only four masks are used to form the gate electrode, the first insulating layer, the active layer, the ohmic contact layer, the source and drain electrodes, the pixel electrode and the second insulating layer.

11. The method according to claim 7, wherein the second insulating layer is a passivation layer.

12. The method according to claim 1, wherein only three masks are used to form the first substrate part.

13. A liquid crystal display having a first substrate part, a second substrate part, and a sealant for attaching the first substrate part and the second substrate part, the liquid crystal display comprising:

a contact area and a common voltage terminal connected to the contact area on the first substrate part, the contact area being exposed at an edge of a region where the sealant is formed, at least a part of the contact area being outside of the sealant;

a common electrode on the second substrate part and exposed at an edge of the region where the sealant is formed; and

a conductive material electrically connecting the contact area of the first substrate part to the common electrode of the second substrate part.

14. The liquid crystal display to claim 13, wherein the conductive material includes a conductive paste.

15. The liquid crystal display to claim 13, wherein the sealant is provided on a region of the first substrate where a passivation layer is formed, and the passivation layer is formed over the contact area.

16. The liquid crystal display to claim 13, wherein the first substrate part comprises:

a substrate;

a gate electrode and a gate line on the substrate, the gate line being arranged in a first direction;

an insulating layer over the substrate;

an active layer and an ohmic contact layer on the insulating layer above a region where the gate electrode is formed;

source and drain electrodes on the ohmic contact layer and a data line formed in a second direction normal to the first direction;

a pixel electrode at least partially overlapped with and electrically connected to the drain electrode;

a passivation layer over a resultant substrate including the pixel electrode.

17. A method for fabricating a liquid crystal display comprising:

attaching a first substrate part having a contact area and a common voltage terminal, the contact area being connected to the common voltage terminal and a second substrate part having a common electrode to form attached substrates;

exposing the contact area provided at an edge portion of the first substrate part by removing an insulating layer over the contact area; and

electrically connecting the contact area of the first substrate part to the common electrode of the second substrate part.

18. The method according to claim 17, wherein exposing the contact area includes etching the insulating layer over contact area using an etch solution.

19. The method according to claim 17, wherein exposing the contact area includes etching the insulating layer over the contact area using a laser.

20. The method according to claim 17, wherein exposing the contact area includes etching the insulating layer over the contact area using plasma.

21. The method according to claim 17, wherein electrically connecting the contact area of the first substrate part to the common electrode of the second substrate part uses a conductive material.

22. The method according to claim 21, wherein the conductive material is in a paste form.

23. The method according to claim 21, wherein the conductive material includes Ag.

24. The method according to claim 21, wherein electrically connecting the contact area of the first substrate part to the common electrode of the second substrate part is performed manually.

25. The method according to claim 21, wherein electrically connecting the contact area of the first substrate part to the common electrode of the second substrate part is performed automatically.

26. The method according to claim 17, wherein the step of forming the first substrate part comprises:

forming a gate electrode and a gate line in a first direction on a substrate;

forming a first insulating layer over the substrate;

forming an active layer and an ohmic contact layer at a region on the insulating layer, the region corresponding to an area above the gate electrode;

forming source and drain electrodes on the ohmic contact layer and a data line in a second direction normal to the first direction;

forming a pixel electrode at least partially overlapped with and electrically connected with the drain electrode; and

forming a second insulating layer over the substrate including the pixel electrode.

27. The method according to claim 26, wherein the step of forming the active layer, the ohmic contact layer and the source and drain electrodes are performed using one mask.

28. The method according to claim 17, wherein attaching the first and second substrate parts use a sealant coated on one of the first and second substrate parts.

29. The method according to claim 28, wherein the contact area is located outside of the sealant.

30. The method according to claim 17, wherein the step of electrically connecting includes coating a conductive material at a side edge portion of the attached substrates to connect the contact area in the first substrate part to the common electrode in the second substrate part.